This severely hydrotreated naphthenic process oil provides good solvency for the rubber and chemical processing industries.

It has a low pour point, a low odor level, excellent color, and resistance to discoloration by heat or ultraviolet light.

	TEST DESCRIPTION		TEST METHOD	resistance to discoloration by heat of SPECIFICATIONS		MARKETING
				Min	Max	VALUES
	Physical Pro	perties				
1	Viscosity, SUS a	Viscosity, SUS at 100°F(37.8℃)		100	121. 0	112
2	Viscosity, SUS at 210°F(98.9°C)		ASTM D 445			38. 1
3	Viscosity, cSt at 40°C(104°F)		ASTM D 341	18. 9	22.8	21.1
4	Viscosity,cSt at 100℃(212°F)		ASTM D 341			3, 5
5	API Gravity,60°F(15.6℃)		ASTM D 1250			24. 6
6	Specific Gravity,60°F(15.6℃)		ASTM D 4052			0.9065
7	Viscosity- Gravity Constant		ASTM D 2501			0.8686
8	Density, lbs/gal at 60°F		ASTM D 1250			7. 549
9	Molecular Weight		ASTM D 2502			298
10	Flash Point, COC, °F(°C)		ASTM D 92	325(163)		350(177)
11	Color, ASTM		ASTM D 6045		1.0	L0. 5
12	Pour Point, °F(°C)		ASTM D 5949		-30(-34)	-60(-51)
13	Volatility, wt%, 225°F (Evap.Loss)		ASTM D 972			10.0
14	Water Content		ERTM-1	PASS		PASS
15	Appearance		ERTM-2	PASS		PASS
	Chemical Pr	operties			1	
1	Acid Number, mg KOH/g		ASTM D 664		0.05	0.01
2	Aniline Point, °F(°C)		ASTM D 611	155.0(68.3)	170. 0(76. 7)	165. 8(74. 3)
3	Sulfur, wt%		ASTM D 4294		0.050	0. 025
4	Sulfur, ppm		ASTM D 4294		500	250
5	Refractive Index, 20°C (68°F)		ASTM D 1218			1. 4951
6	UV absorptivity at 260nm		ASTM D 2008		2. 50	1.70
	Clay-Gel, wt%	Asphaltenes	ASTM D 2007			<0.1
7		Polar Compounds				0.4
7		Aromatics				35. 4
		Saturates				64. 2
	Carbon Type	Ca	ASTM D 2140			10
8	Carbon Type Analysis,%	Cn				47
		Ср				43
	Health and	Safety Properties	,		<u> </u>	
1	Polycyclic Aromatic Compounds, wt%		IP 346		3	< 3
2	Modified Ames Assay		ASTM E 1687	PASS		PASS
3	FDA Regulation		21 CFR 178. 3620 (C)	PASS		PASS

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